



ASML

**ASML reiterates H1 2012 expectation,
sees stable sales in Q3**

ASML 2012 First Quarter Results

Veldhoven, the Netherlands, April 18, 2012

Safe Harbor

"Safe Harbor" Statement under the US Private Securities Litigation Reform Act of 1995: the matters discussed in this document may include forward-looking statements, including statements made about our outlook, realization of systems backlog, IC unit demand, financial results, average selling price, gross margin and expenses, dividend policy and intention to repurchase shares.

These forward looking statements are subject to risks and uncertainties including, but not limited to: economic conditions, product demand and semiconductor equipment industry capacity, worldwide demand and manufacturing capacity utilization for semiconductors (the principal product of our customer base), including the impact of general economic conditions on consumer confidence and demand for our customers' products, competitive products and pricing, the impact of manufacturing efficiencies and capacity constraints, the continuing success of technology advances and the related pace of new product development and customer acceptance of new products, our ability to enforce patents and protect intellectual property rights, the risk of intellectual property litigation, availability of raw materials and critical manufacturing equipment, trade environment, changes in exchange rates, available cash, distributable reserves for dividend payments and share repurchases, and other risks indicated in the risk factors included in ASML's Annual Report on Form 20-F and other filings with the US Securities and Exchange Commission.



Agenda

- Business summary
- Market
- ASML technology strategy
- Outlook



Business summary



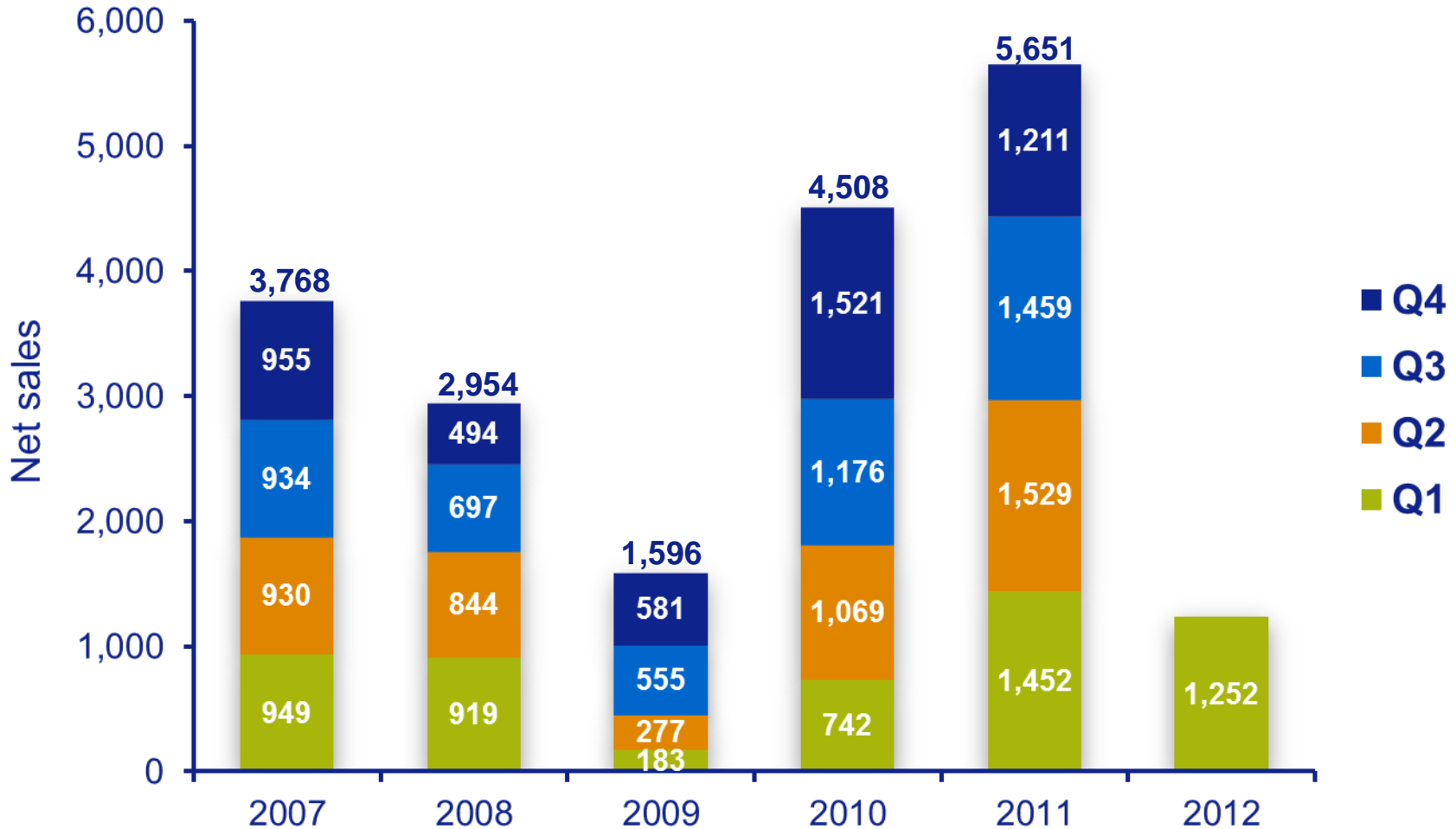
Q1 results - highlights

- Net sales of € 1,252 million, 52 systems sold valued at € 1,050 million, net service and field option sales at € 202 million
- Gross margin of 41.8%*, excluding EUV 43.3%
- Operating margin of 25.8%
- Net bookings of € 865 million, 36 systems
- Backlog at € 1,598 million, 56 systems
- Generated € 396 million cash from operations

* Final EUV NXE:3100 revenue recognized

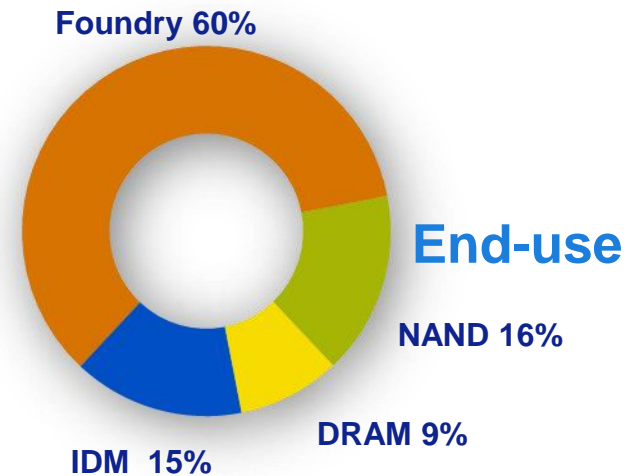
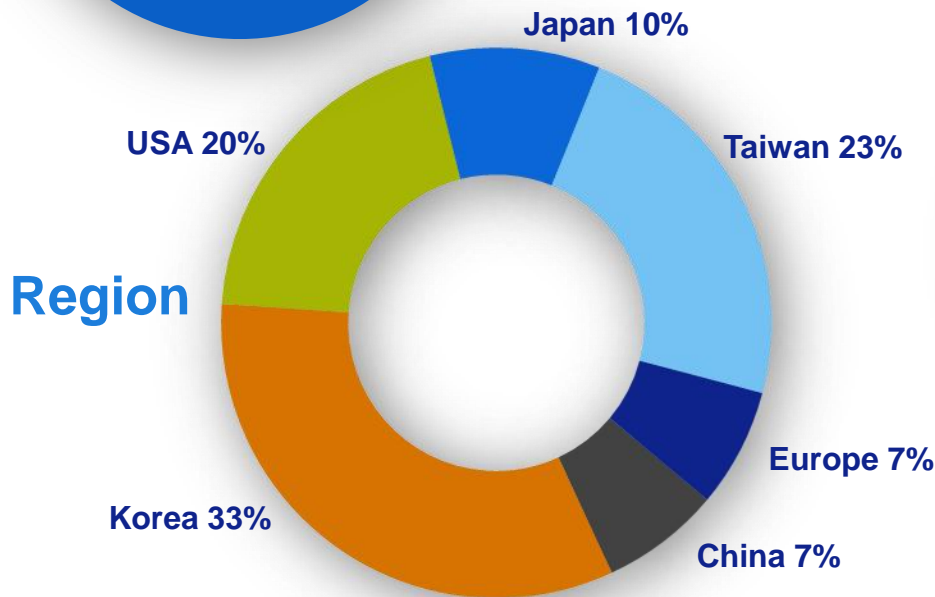
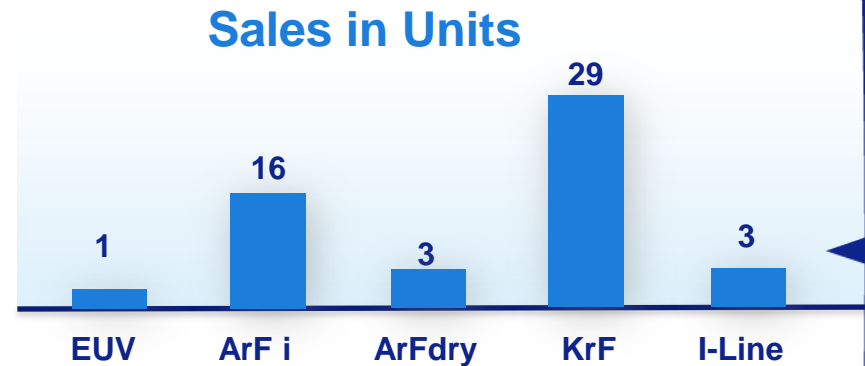
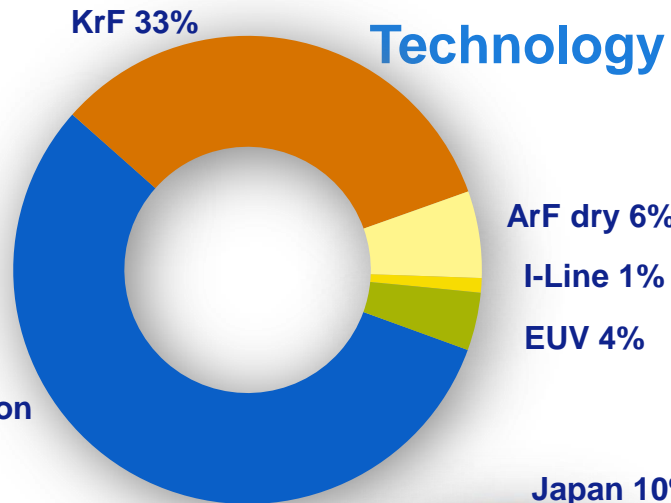
Net bookings and backlog numbers are excluding EUV.

Total net sales M€



Numbers have been rounded for readers' convenience.

Net system sales breakdown in value: Q1 2012



Numbers have been rounded for readers' convenience.

/ Slide 7



ASML

Consolidated statements of operations M€

	Q4 11	Q1 12
Net sales	1,211	1,252
Gross profit	496	524
Gross margin %	41.0%	41.8%
R&D costs	150	145
SG&A costs	56	55
Income from operations	290	324
Operating income %	23.9%	25.8%
Net income	285	282
Net income as a % of net sales	23.5%	22.5%
Earnings per share (basic) €	0.69	0.68

Numbers have been rounded for readers' convenience.

Key financial trends 2011 – 2012

Consolidated statements of operations M€

	Q1 11	Q2 11	Q3 11	Q4 11	Q1 12
Net Sales	1,452	1,529	1,459	1,211	1,252
Gross profit	649	690	613	496	524
Gross margin %	44.7%	45.1%	42.1%	41.0%	41.8%
R&D costs	145	145	150	150	145
SG&A costs	54	51	56	56	55
Income from operations	450	494	407	290	324
Operating income %	31.0%	32.3%	27.9%	23.9%	25.8%
Net income	395	432	355	285	282
Net income as a % of net sales	27.2%	28.3%	24.4%	23.5%	22.5%
Units sold	63	63	55	41	52
ASP new systems	22.5	22.7	27.1	27.4	22.1
Net bookings value	845	840	514	710	865

Numbers have been rounded for readers' convenience.



Cash flows M€

	Q4 11	Q1 12
Net income	285	282
<i>Adjustments to reconcile net income to net cash flows from operating activities:</i>		
Impairment and obsolescence	26	24
Depreciation and amortization	40	50
Deferred income taxes	28	22
Other non-cash items	4	4
Change in assets and liabilities	(251)	14
Net cash provided by operating activities	132	396
Net cash used in investing activities	(94)	(51)
Net cash used in financing activities	(154)	(120)
Total FX effects	10	(4)
Net increase (decrease) in cash and cash equivalents	(106)	221

Numbers have been rounded for readers' convenience.



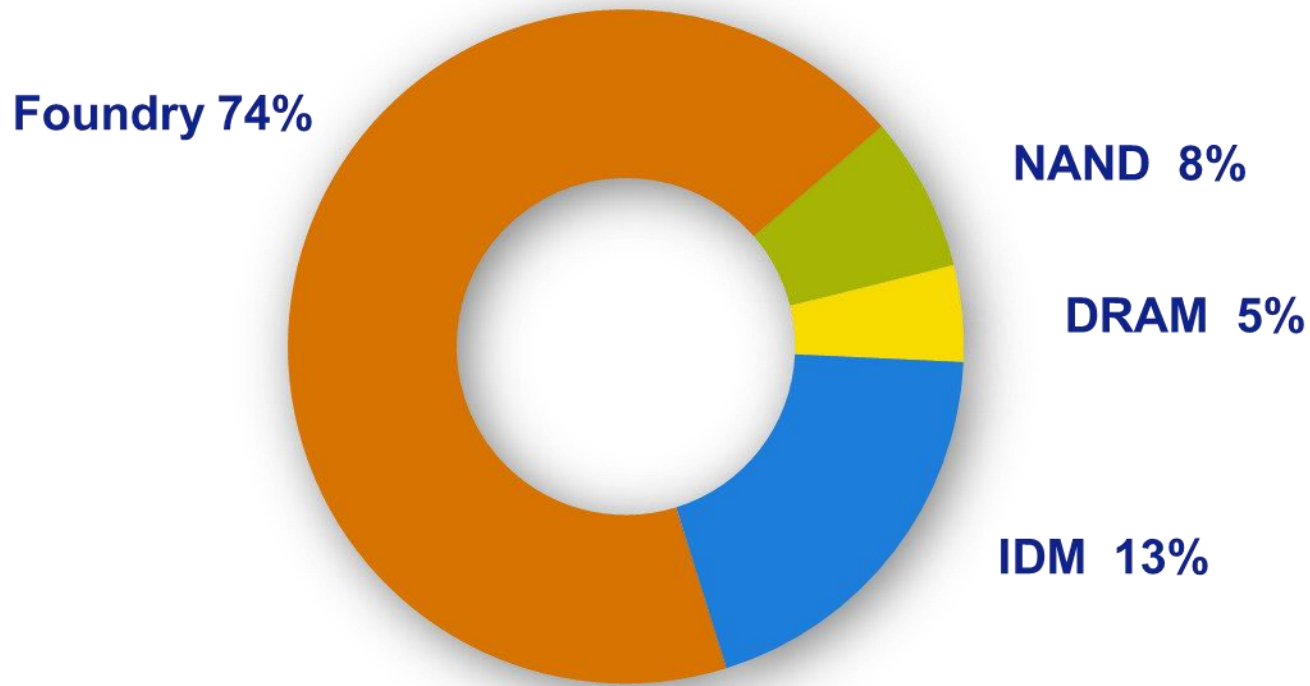
Balance sheets M€

Assets	Dec 31st, 2011		Apr 1st, 2012	
Cash and cash equivalents	2,732	38%	2,953	40%
Accounts receivable, net	881	12%	761	10%
Finance receivables, net	79	1%	79	1%
Inventories, net	1,625	22%	1,608	22%
Other assets	545	7%	551	8%
Tax assets	191	3%	171	2%
Fixed assets	1,208	17%	1,276	17%
Total assets	7,261	100%	7,399	100%
Liabilities and shareholders' equity				
Current liabilities	2,233	31%	2,091	28%
Non-current liabilities	1,584	22%	1,696	23%
Shareholders' equity	3,444	47%	3,612	49%
Total liabilities and shareholders' equity	7,261	100%	7,399	100%

Numbers have been rounded for readers' convenience.



Bookings activity by sector - total net value M€ 865



- Net booked - 31 new tools at € 842 million
- 5 used tools at € 23 million

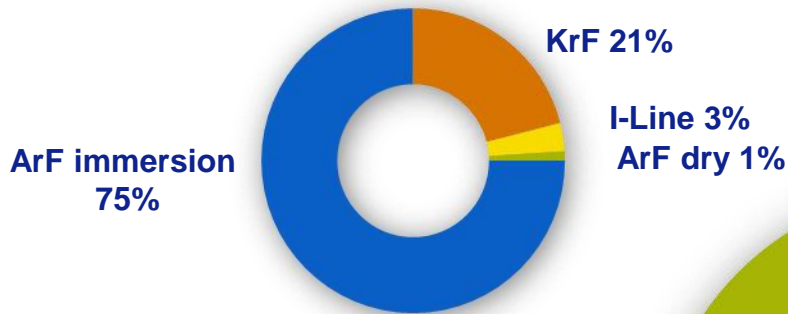
Numbers have been rounded for readers' convenience.

/ Slide 12

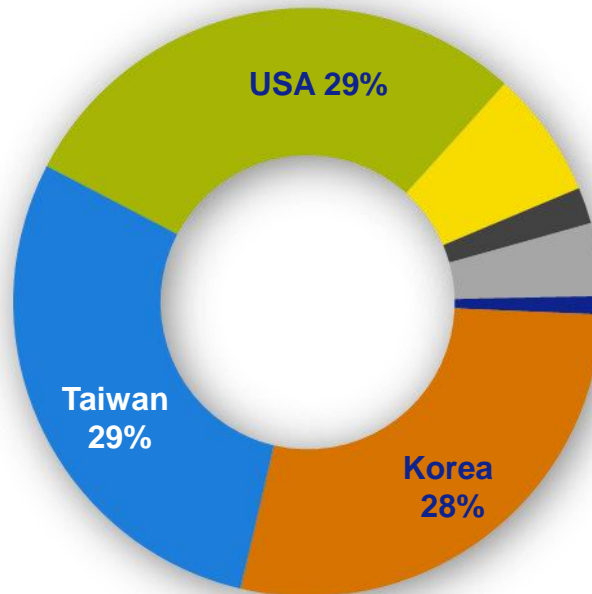
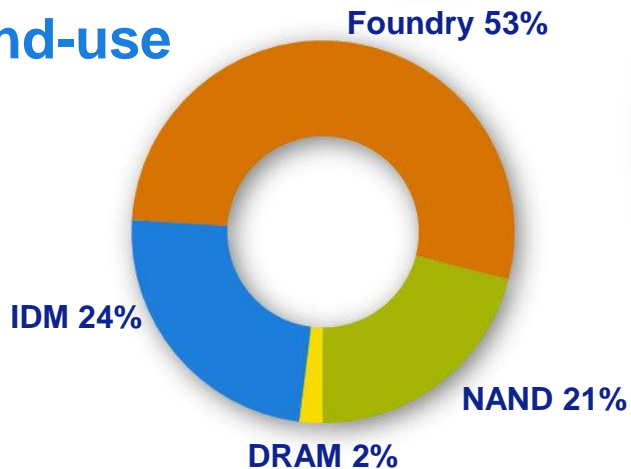
Backlog in value per Apr 1st, EUV not included

Total value M€ 1,598

Technology



End-use



Japan 7%

Singapore 2%

Europe 4%

China 1%

Region
(ship to location)

	New systems	Used systems	Total systems
Units	46	10	56
Value M€	1,546	52	1,598
ASP M€	33.6	5.2	28.5

- 91% of backlog carry shipment dates in the next 6 months

Numbers have been rounded for readers' convenience.

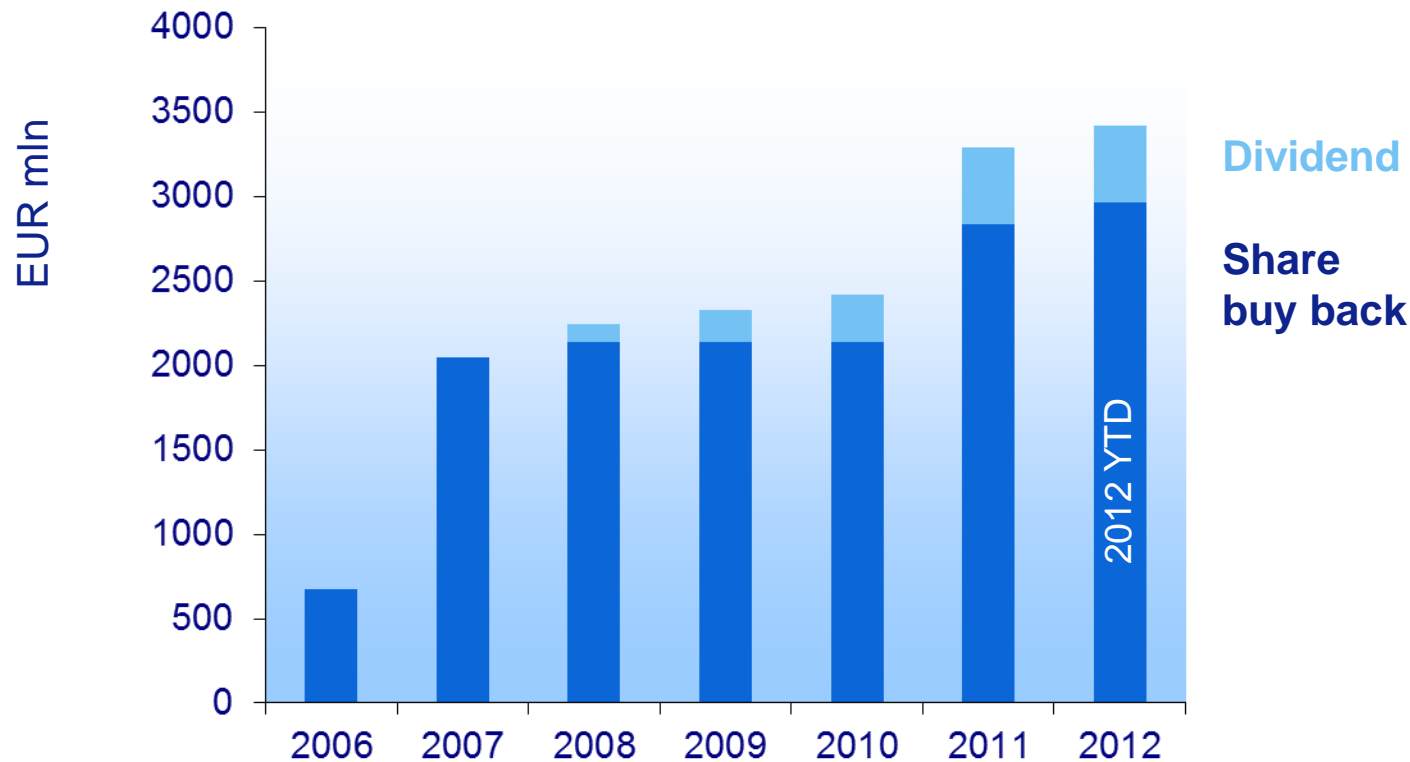


Cash return to shareholders

- Dividend of € 0.46 per ordinary share will be proposed during the AGM April 25th
- 74% of € 1,130 million share buy back program executed end of Q1
 - Bought back 4.1 million shares worth € 139 million in Q1 '12
 - Purchased shares are/will be cancelled
- Initiate buy back program of up to 2.2 million shares to cover outstanding employee stock and option plans later this year
 - These shares will be held as treasury shares
- Reiterate our policy to return excess cash to shareholders through dividend payments and share buy backs



ASML has returned nearly € 3.5 billion cash in the past 6 years



- Repurchased more than 147 million shares since 2006 representing approx. 31% of outstanding shares



ASML – #1 semi equipment supplier in 2011

2011 Top Semiconductor Equipment Suppliers
(worldwide sales, semiconductor equipment and service, \$M)

2011 Rank	AOW	COMPANY	2009	2010	2011	11/'10 Growth
1	EU	ASML	2267.9	5973.1	7877.1	32%
2	NA	Applied Materials*	3507.9	7284.0	7437.8	2%
3	JA	Tokyo Electron	2323.7	5261.3	6203.3	16%
4	NA	KLA-Tencor	1316.1	2431.7	3106.2	26%
5	NA	Lam Research	1198.0	3004.6	2804.1	-7%
6	JA	Dainippon Screen Mfg. Co.	887.1	1727.3	2104.9	22%
7	JA	Nikon Corporation	1342.3	1517.3	1645.5	6%
8	JA	Advantest**	430.0	1134.2	1446.7	26%
9	EU	ASM International	693.9	1416.3	1443.0	2%
10	NA	Novellus Systems	581.9	1316.7	1318.7	0%
11	JA	Hitachi High-Technologies	474.4	910.5	1138.7	25%
12	NA	Teradyne	552.4	1406.5	1106.2	-21%
13	NA	Varian Semiconductor Equipment***	395.9	971.8	1096.3	13%
14	JA	Hitachi Kokusai Electric	212.8	626.4	838.4	34%
15	NA	Kulicke & Soffa	262.4	745.9	780.9	5%
Total Top 15			16446.7	35727.8	40347.7	
<i>y-o-y growth</i>				<i>117%</i>	<i>13%</i>	

* Applied Materials includes Varian revenues for Nov 1 to Dec 31, 2011

** Advantest includes Verigy's revenues from July 1 to Dec 31, 2011

*** Varian includes revenues as an independent company from Jan 1 to Oct 31, 2011

2011 Exchange rates:

Source: VLSIresearch, data reproduced by ASML with permission



Market



Business environment

- Litho sales is driven mainly by demand from Logic (Foundries and IDM's), which will represent the majority of our sales in the next 2 quarters
- Demand for 28 nm in Logic continues to be large and structural and will be accompanied by the start of pre-production for 20 nm late in 2012
- For memory we expect technology demand for sub 20 nm NAND, sub 30 nm DRAM later this year
- Our sales will include both TWINSCAN immersion technology and KrF tools driven by sustained capacity build in Logic



ASML technology strategy



Dual product strategy

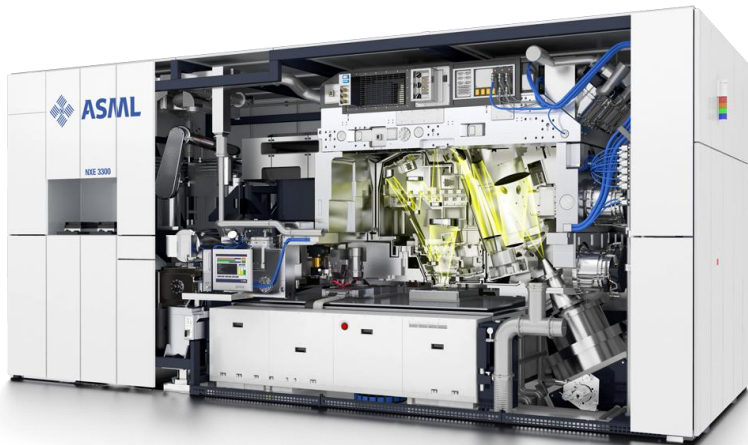
TWINSKAN NXT - Immersion

- Extendibility in throughput, overlay and imaging (CDU)
- Optimized for multi pass patterning



TWINSKAN NXE - EUV

- Preparing EUV platform for volume manufacturing of critical layers
- Extendibility in imaging to 10nm and beyond



Q1 immersion platform highlights

- **NXT:1950i achieved a new productivity milestone of over 4,500 wafers in a single day in customer's fab**
- **Shipped first systems with throughput of 230 wafers per hour at 96 shots, 20% productivity improvement**
- **Installed base of NXT tools is 142 machines**



ASML

**TWINSCAN
1950i**

Optics by
zeiss

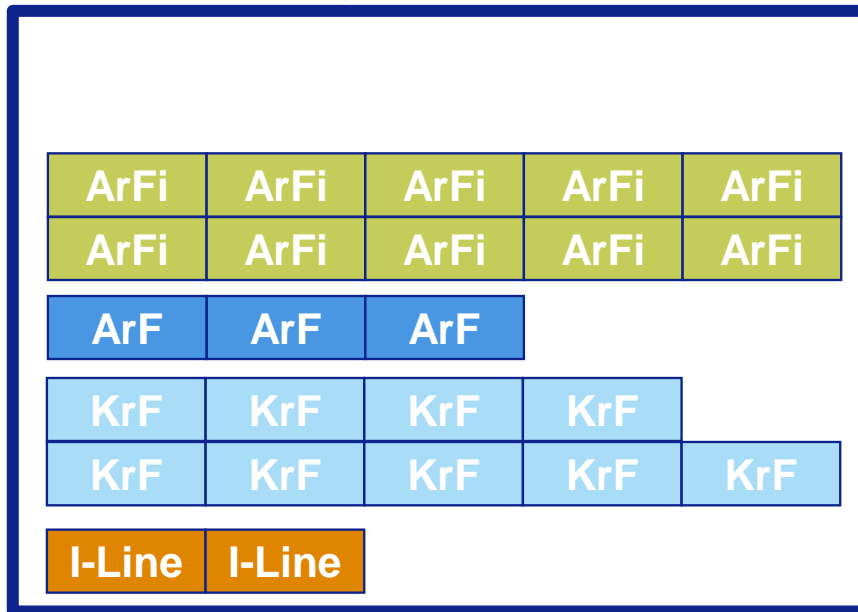


ASML

Shrink drives more exposures and litho system demand

Logic fab 45k wafers/month

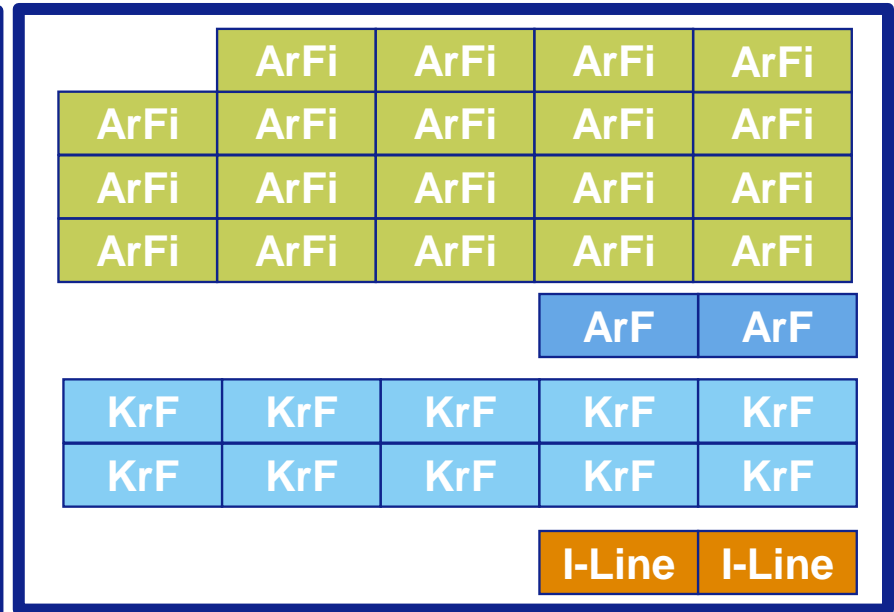
Logic 32/28nm



37 litho layers
(14 Critical– 23 nonCritical)

38 litho exposures
(13 SE, 1 LELE, 23 nonCritical)

Logic 22/20nm



40 litho layers
(19 Critical – 21 nonCritical)

52 litho exposures
(8 SE, 10 LELE, 1LELELE, 21 nonCritical)

8% layer increase



37% exposure increase

All scenarios are based on “typical” process using 2012 system productivity levels
Customers process and wafer start requirements will vary

All 2nd generation EUV systems delivered to customers



System 1



System 4



System 2



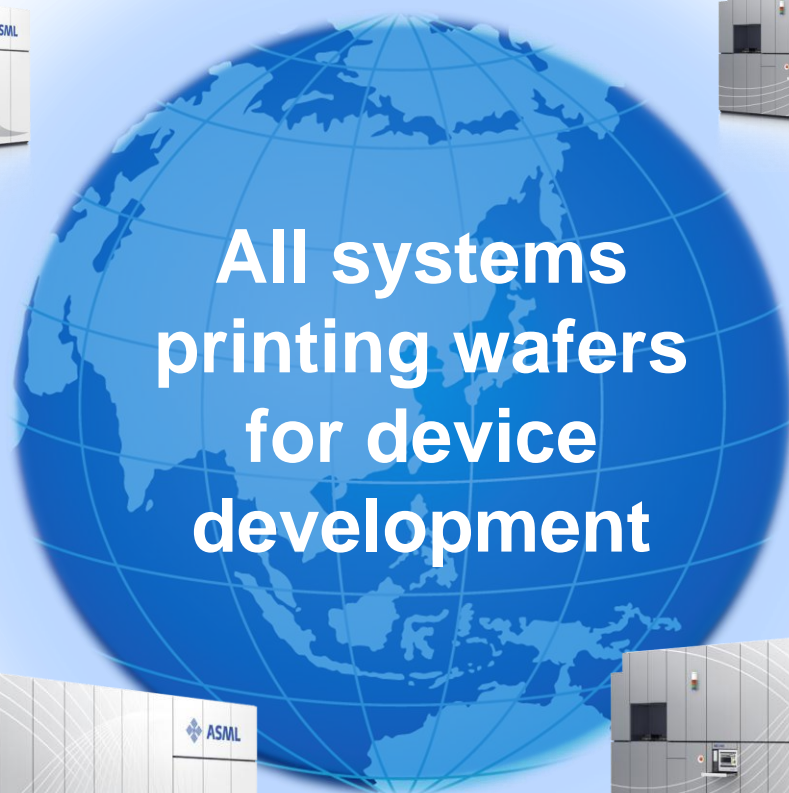
System 5



System 3



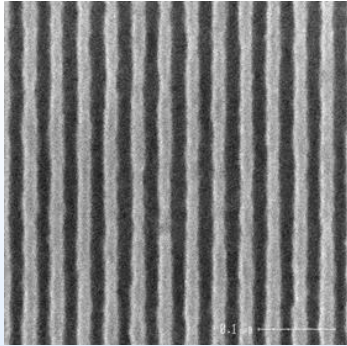
System 6



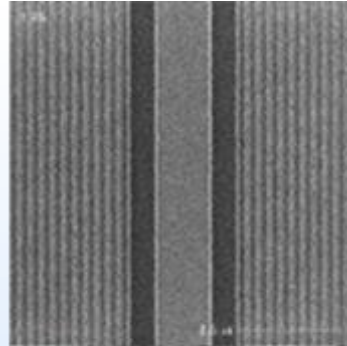
All systems
printing wafers
for device
development



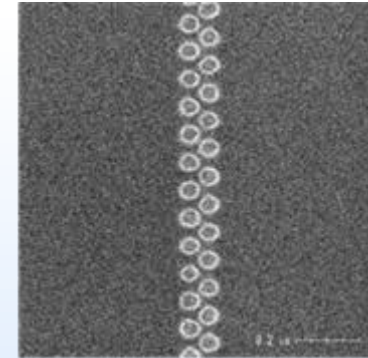
NXE:3100 imaging performance proven for various customer applications



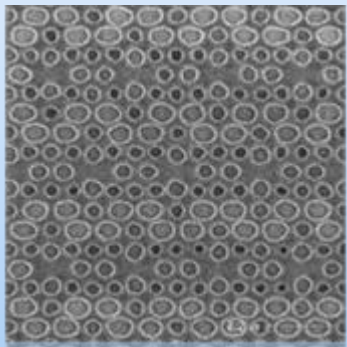
16nm dense lines



**27 nm Gate Layer
Flash**

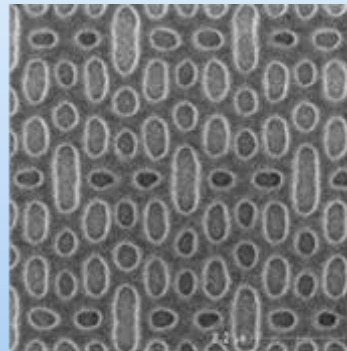


Flash staggered contact layer
Bitline pitch = 44 nm (1:1.2)
CH pitch = 74.4 nm



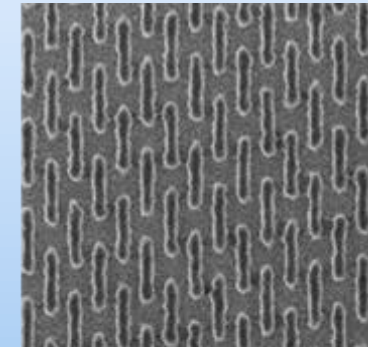
**Sub 16 nm node
SRAM Contact Hole**

0.038 μ m² bit cell-size,
hp 30/32 nm



**Sub 16 nm node
SRAM metal-1**

0.038 μ m² bit cell-size,
hp 30/32 nm



30 nm Brickwall DRAM



The background image shows two technicians in white cleanroom suits, hoods, and masks working on a piece of equipment in a cleanroom environment. The technician on the left is wearing glasses and has a radiation warning symbol on his sleeve. The technician on the right is also wearing a radiation warning symbol on his sleeve. They are both looking down at the equipment they are working on.

EUUV highlights Q1

- Supplier has demonstrated 30 Watts laser power at high duty cycle with acceptable dose control for a sustained period of time
- In addition progress demonstrated on light source with 50 watts raw laser power, successfully applying pre-pulse technology
- Stable overlay performance of < 2 nm achieved
- 9,000 wafers exposed on customer EUV tools to date



ASML roadmaps support shrink to <10nm

EUV insertion will vary by sector

	2011 - 2012	2013 - 2014	2015 - 2016	2017 - 2018
Logic	22 - 20nm	16 - 14nm	11 - 10nm	8 - 7nm
DRAM	38 - 32nm	27 - 22nm	22 - 16nm	16 - 14nm
Flash	24 - 19nm	16 - 14nm	13 - 11nm	< 10nm

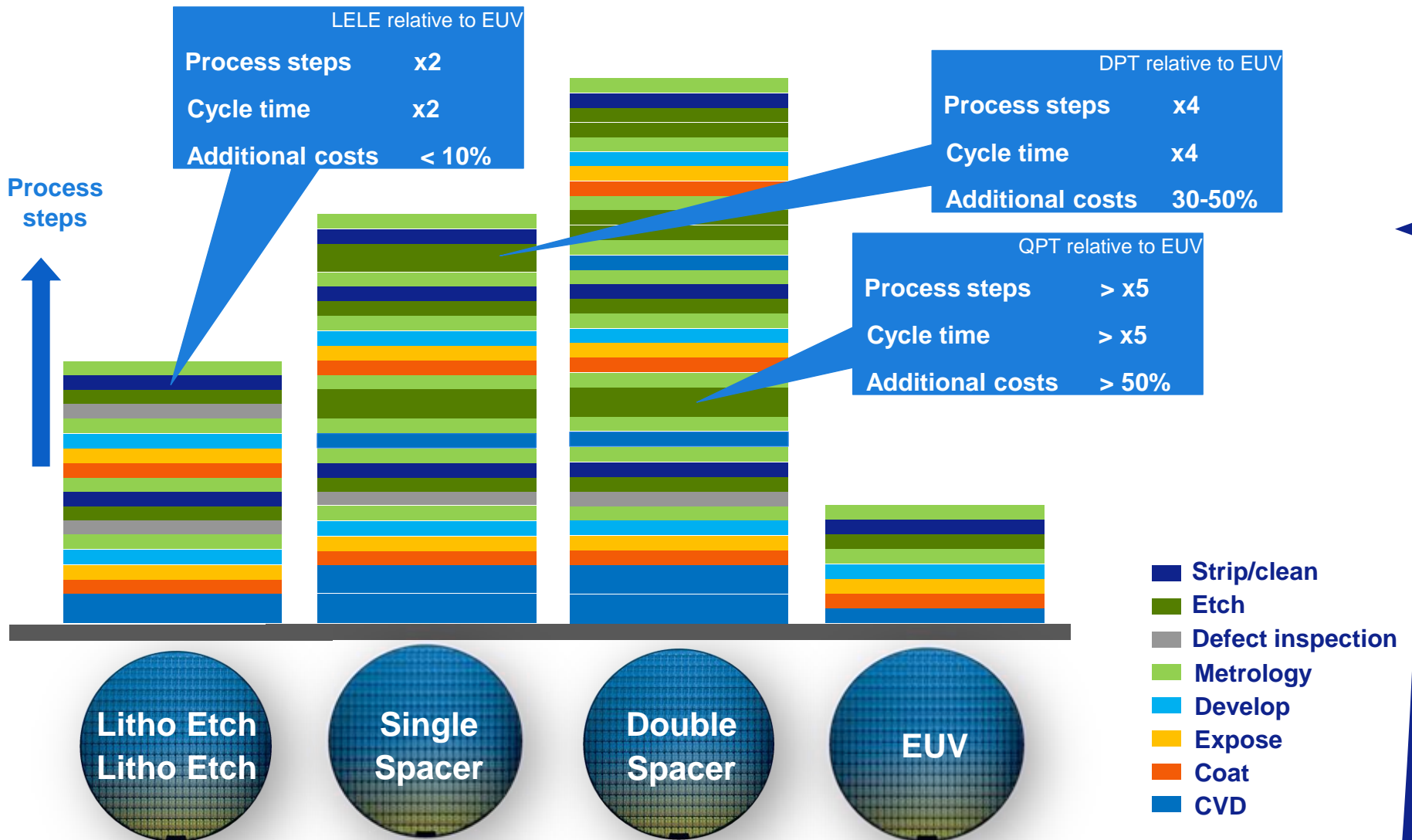
ArFi: Single and double exposure, spacer and double spacer

EUV: Single exposure

- EUV starts introduction for critical layers in the low 2x nm technology nodes in 2013 -2014 and mid 1x nm in 2015 and beyond
- Immersion will continue to be used
 - for critical layer imaging in double patterning mode
 - for mid-critical layers in single patterning mode



EUV simplifies process and reduces costs and cycle time



Data is based on Customer interaction
/ Slide 27





ASML

Building for EUV volume production

New EUV factory at ASML for ~3x capacity increase



Existing EUV offices & manufacturing, 8 cabins. 

New EUV offices & manufacturing, 15 cabins. 

Status EUV

- First shipment of the NXE:3300B production system is planned for Q4 2012 with revenue recognition expected starting early 2013
- Next batch of orders currently being negotiated
- Proven imaging and overlay performance of NXE:3100 platform supports current customer device and process development for 2x nm node
- Programs defined to improve efficiency of the system to reach our target of 60 wafers per hour in H2 2012
- EUV delivers:
 - Single exposure shrink, fewer design restrictions, with less fab complexity in less fab space
 - Extendable for many nodes to come



Outlook



ASML

Q2 Outlook

- Net sales around € 1.2 billion
- Gross margin about 43%
- R&D costs at € 145 million
- SG&A costs at € 55 million

ASML sees stable sales at current levels in Q2 and Q3 with signs that Logic will continue its strong demand trend for the remainder of the year





ASML

